



Attorney Docket: 081468-03
Client Reference: P-1942.063-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 8455

HOFFMAN ET AL.

Application No.: 10/759,699

Group Art Unit: 2873

Filed: January 19, 2004

Examiner: HASAN, MOHAMMED A.

Title: CORRECTION OF BIREFRINGENCE IN CUBIC CRYSTALLINE OPTICAL SYSTEMS

February 16, 2005

REQUEST FOR RETURN OF INITIALED PTO-1449

Mail Stop ISSUE FEE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

The Applicants respectfully request that a copy of the PTO-1449, filed November 22, 2004, be returned with the Examiner's initials in the left column per MPEP § 609. A copy of the PTO-1449, as originally filed, is enclosed.

Respectfully submitted,
PILLSBURY WINTHROP LLP

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Atty. Dkt. No.	M#	Client Ref.
	310701	P-1943.063-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: HOFFMAN et al.

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Examiner: M. HASAN Group Art Unit: 2873

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	AR	5,410,375	04/1995	Fiala			
	BR	6,366,404	04/2002	Hiraiwa et al.			
	CR	6,411,384	06/2002	Sakuma et al.			
	DR	6,417,974	07/2002	Schuster			
	ER	6,583,931	06/2003	Hiraiwa et al.			
	FR	6,672,109	01/2004	Hiraiwa			
	GR	6,683,729	01/2004	Schuster			
	HR	6,697,199	02/2004	Gerhard et al.			
	IR	6,728,043	04/2004	Gruner et al.			
	JR	6,775,063	08/2004	Shiraishi			
	KR	2002/0085176	07/2002	Hiraiwa et al.			
	LR	2002/0149855	10/2002	Schuster			
	MR	2002/0186355	12/2002	Omura			
	NR	2003/0000453	01/2003	Unno et al.			
	OR	2003/0007253	01/2003	Schuster et al.			
	PR	2003/0012724	01/2003	Burnett et al.			
	QR	2003/0063393	04/2003	Omura			

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						Enclosed	No	Enclose	No
	RR	DE 101 23 725	11/2002	Germany	Wagner et al.			X	
	SR	DE 101 23 727	11/2002	Germany	Brunotte et al.			X	
	TR	DE 101 25 487	01/2003	Germany	Brunotte et al.			X	
	UR	DE 101 27 320	12/2002	Germany	Brunotte et al.	X			
	VR	DE 102 10 782	10/2003	Germany	Krähmer et al.	X			
	WR	2002-302628	10/2002	Japan	Mitsuhiko et al.	X			
	XR	2003-050349	02/2003	Japan	Naomasa et al.	X			
	YR								
	ZR								
	AAR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

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*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
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	DDR 2003/0086171	05/2003	McGuire			
	EER 2003/0089299	05/2003	Obara et al.			
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	GGR 2003/0112501	06/2003	Sakuma			
	HHR 2003/0128349	07/2003	Unno			
	IIR 2003/0147061	08/2003	Omura			
	JJR 2003/0197946	10/2003	Omura			
	KKR 2003/0234981	12/2003	Hoffman et al.			
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	NNR 2004/0004771	01/2004	Omura			
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	QQR 2004/0036971	02/2004	McGuire, Jr.			
	RRR 2004/0036985	02/2004	McGuire, Jr.			
	SSR 2004/0105170	06/2004	Krahmer et al.			
	TTR 2004/0136084	07/2004	Unno			

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						Enclosed	No	Enclose	No
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	VVR WO 02/093257	11/2002	WIPO	Brunotte et al.		X			
	WW WO 03/003429	01/2003	WIPO	Omura et al.		X			
	XXR WO 03/007046	01/2003	WIPO	Yamaguchi		X			
	YYR WO 03/046634	06/2003	WIPO	Omura et al.		X			
	ZZR WO 03/077011	09/2003	WIPO	Fiolka et al.					
	AAA WO 03/077007	09/2003	WIPO	Goehnermeier et al.		X			
	BBB WO 03/088330	10/2003	WIPO	Yamaguchi		X			
	CCC WO 04/008254	01/2004	WIPO	Yamada					
	DDD								

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DR	Burnett et al., "Intrinsic Birefringence in Calcium Fluoride and Barium Fluoride," <i>Rapid Communications</i> , Physical Review B, Vol. 64, November 29, 2001, pp. 241102-1 - 4.				
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	QR					

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SR	Unno et al., "Analyses of Imaging Performance Degradation Caused by Birefringence Residual in Lens Materials," <i>Optical Microlithography XIV</i> , Proceedings of SPIE, Vol. 4346, 2001, pp. 1306-1317.				
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